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(12) **United States Design Patent** (10) **Patent No.:** **US D968,030 S**
Li (45) **Date of Patent:** **** Oct. 25, 2022**

(54) **MASK**
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(52) **U.S. Cl.**
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(58) **Field of Classification Search**
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D2/500, 501, 502, 503, 505, 506, 508;
D24/110.1, 110.2; D21/660
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1/046; A63B 71/08; A63B 71/10; A63B
71/105; A61F 9/04; A61F 9/06; A61F
9/029; A41D 13/11; A41D 13/1107;
A41D 13/1161; A41D 13/1169; A41D
13/1176; A41G 7/00; A41G 7/02
See application file for complete search history.

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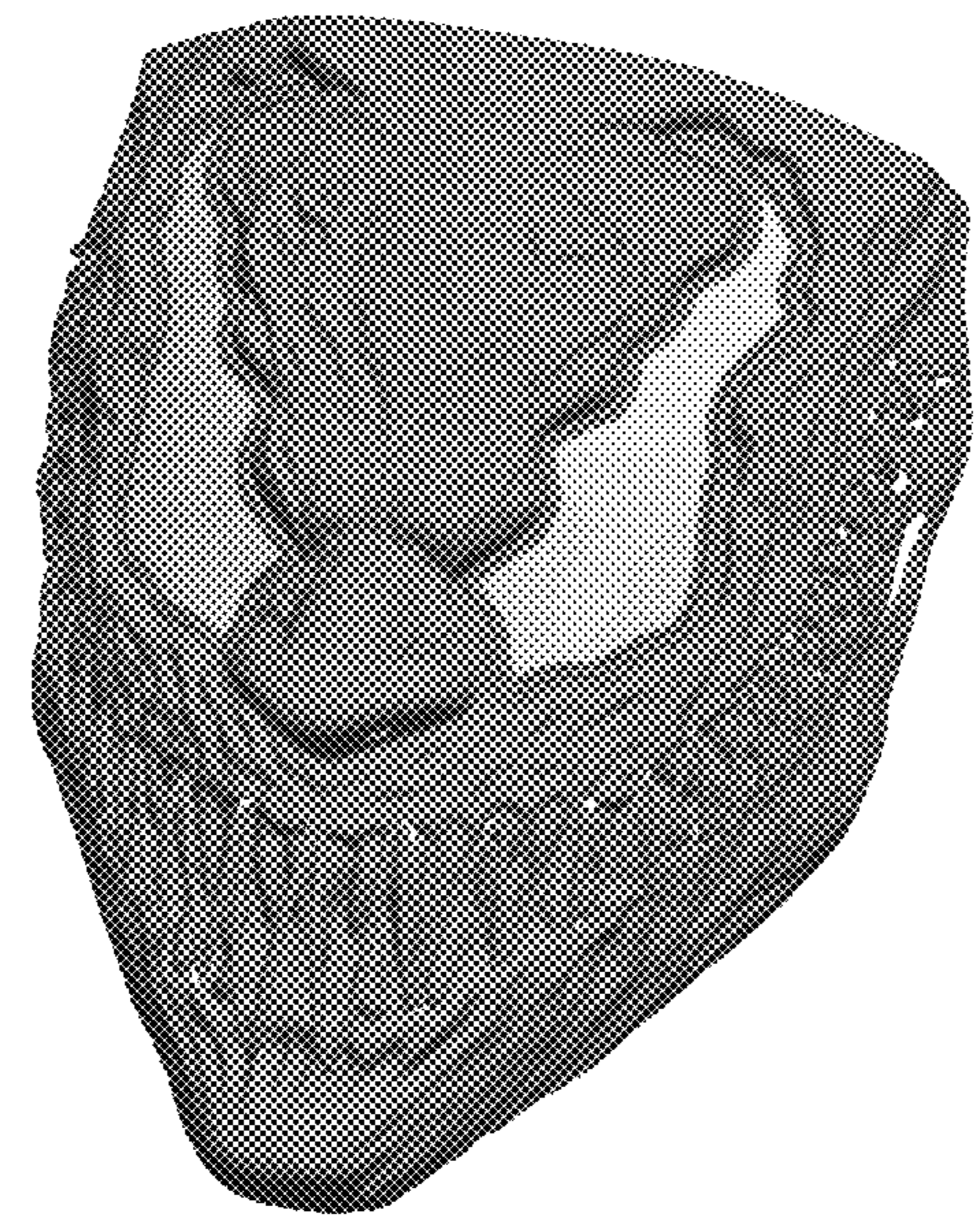
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(57) **CLAIM**
The ornamental design for a mask, as shown and described.

DESCRIPTION

FIG. 1 is a perspective view of a mask, showing my new design;
FIG. 2 is a front view thereof;
FIG. 3 is a rear view thereof;
FIG. 4 is a left side view thereof;
FIG. 5 is a right side view thereof;
FIG. 6 is a top plan view thereof; and,
FIG. 7 is a bottom plan view thereof.

1 Claim, 7 Drawing Sheets



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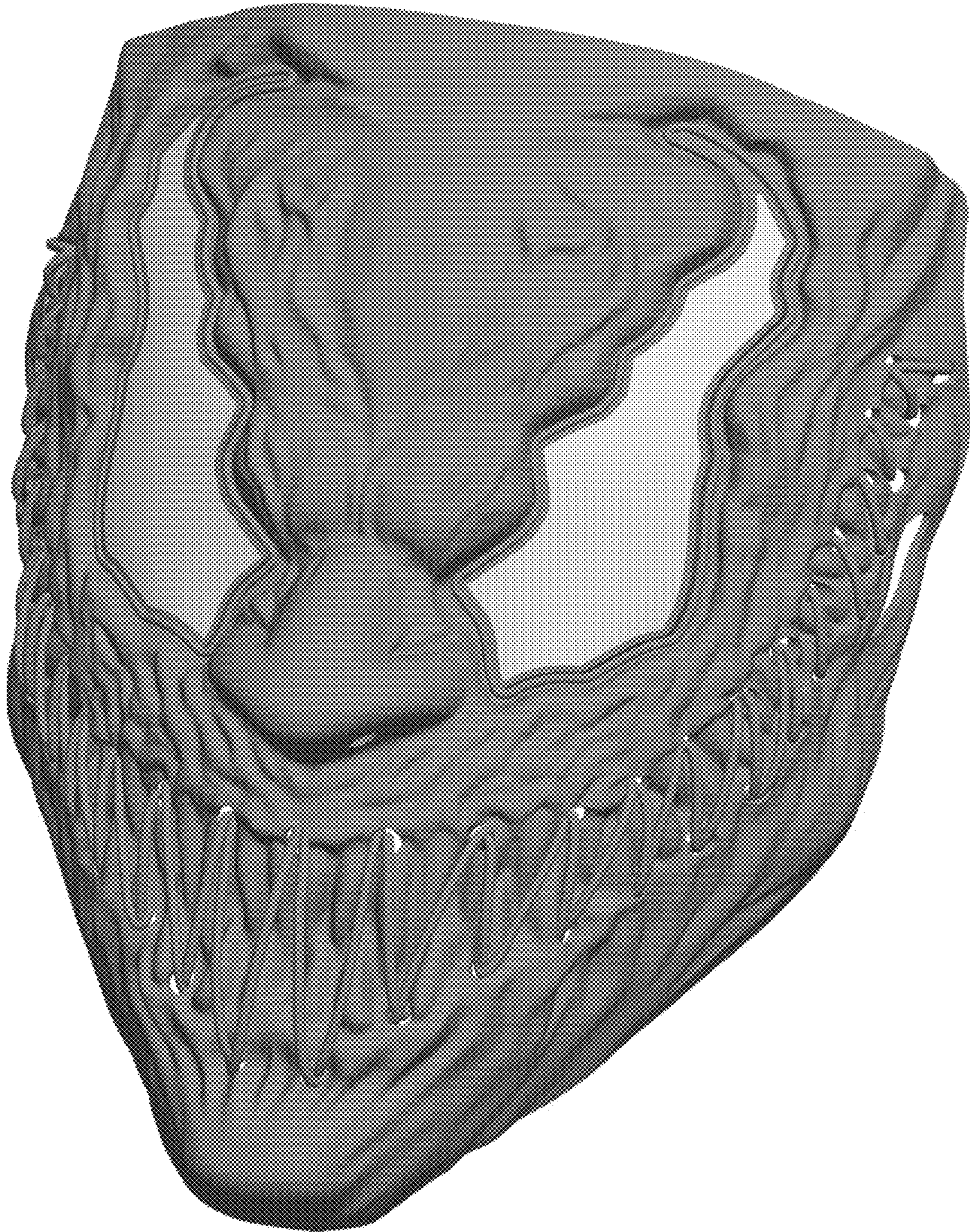


FIG. 1

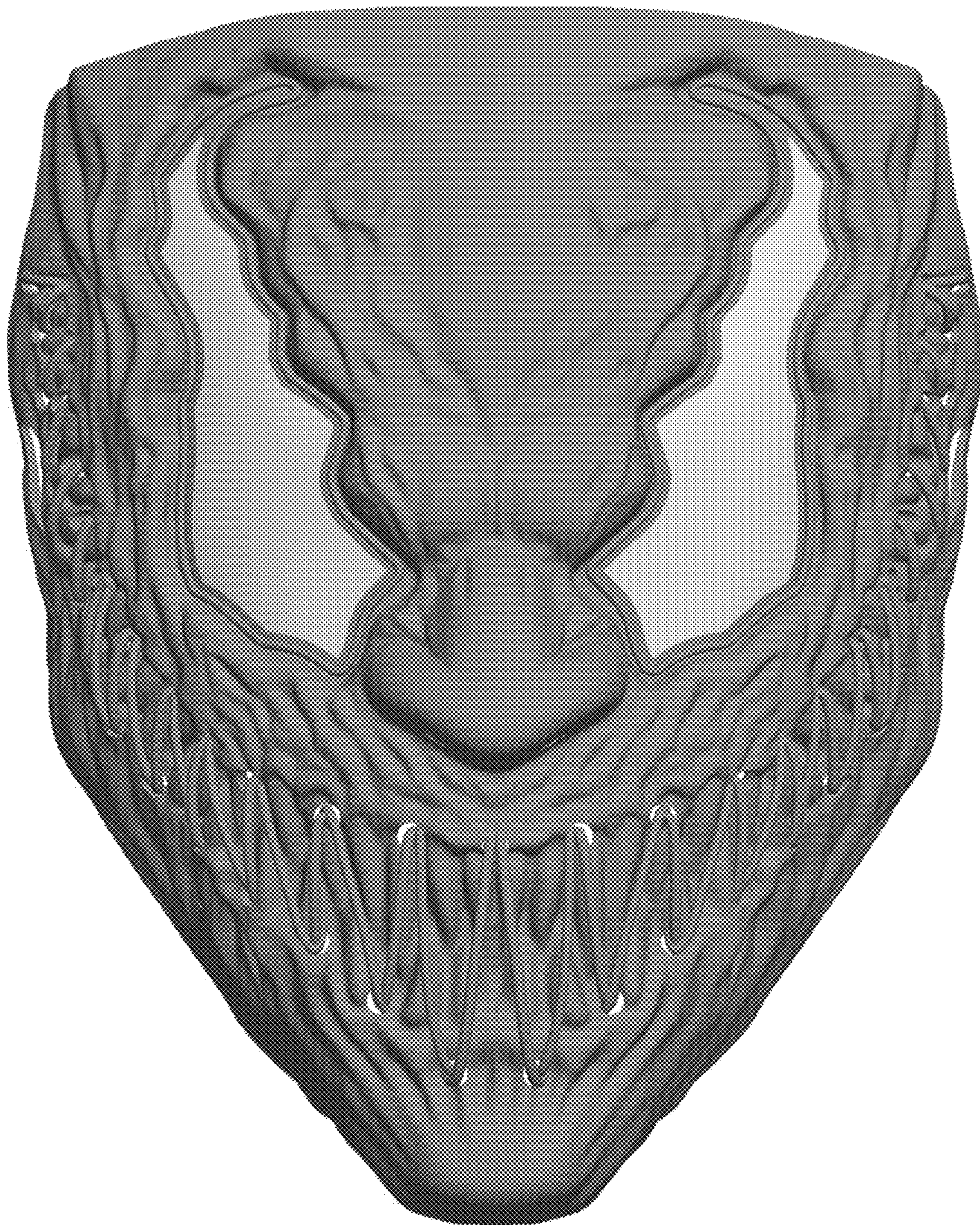


FIG. 2

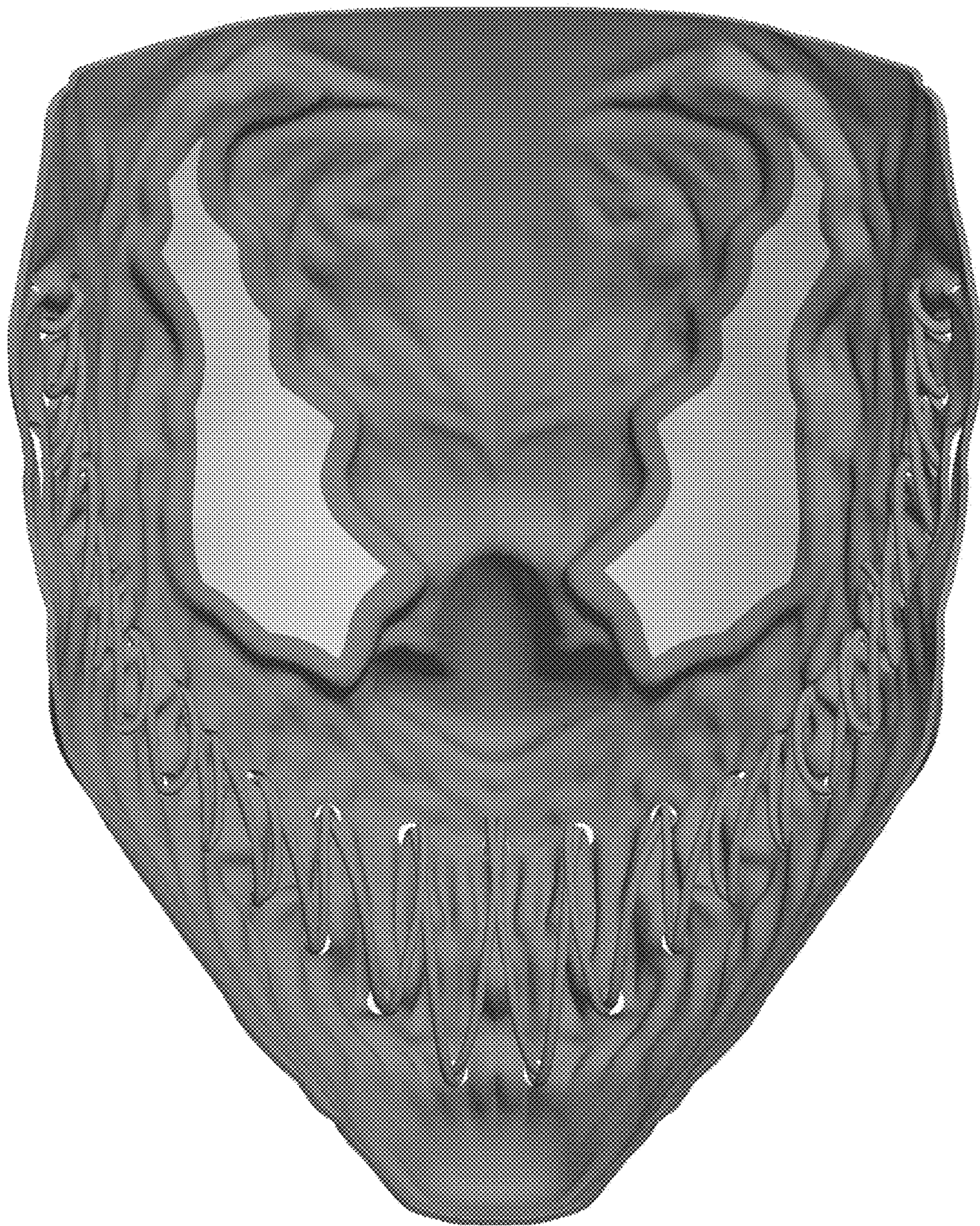


FIG. 3

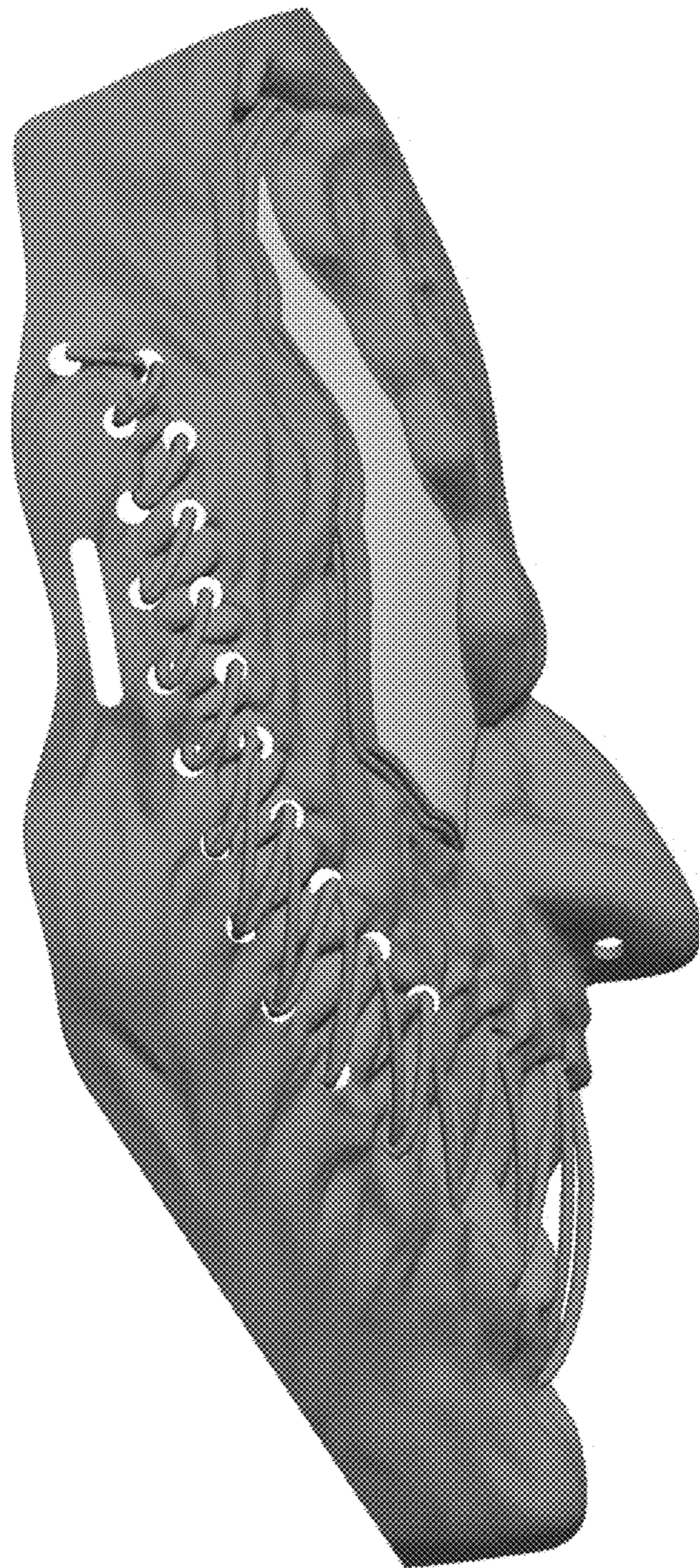


FIG. 4

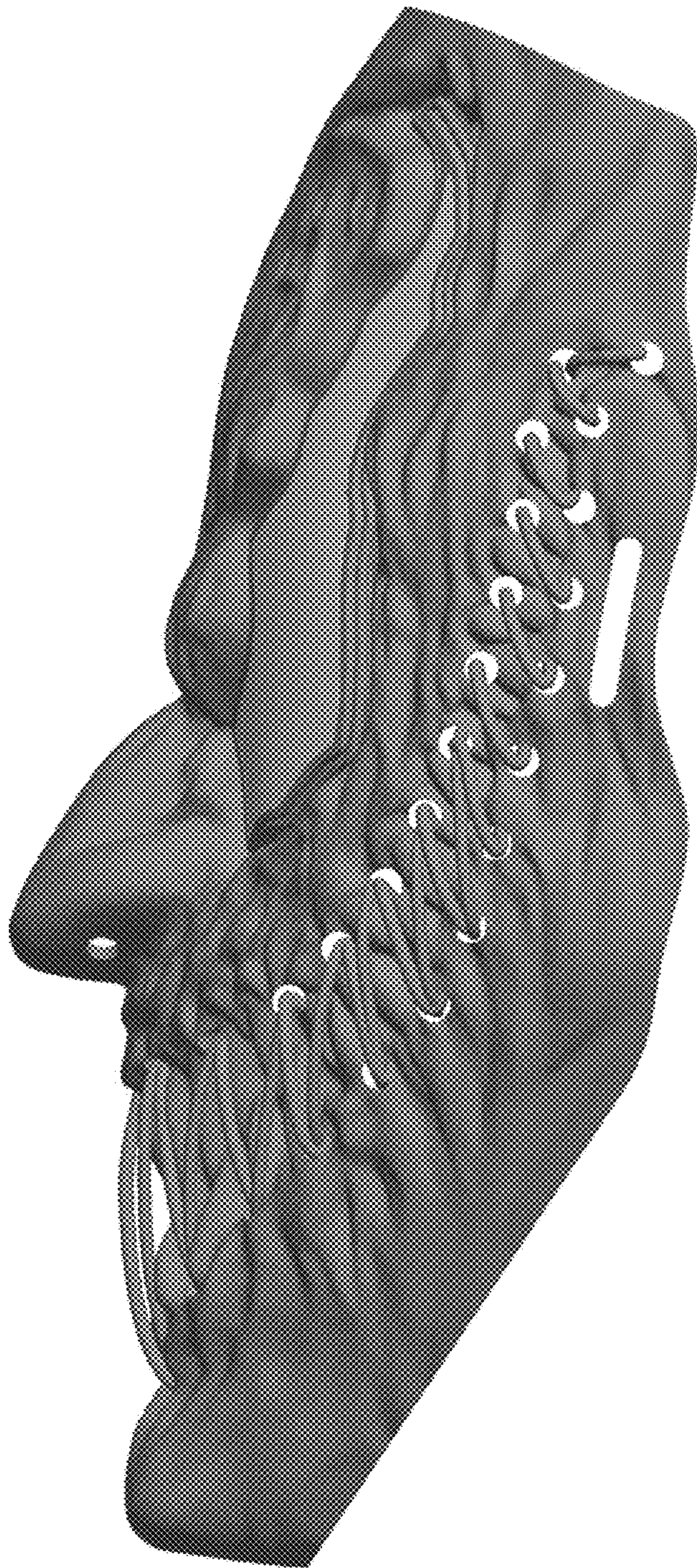


FIG. 5

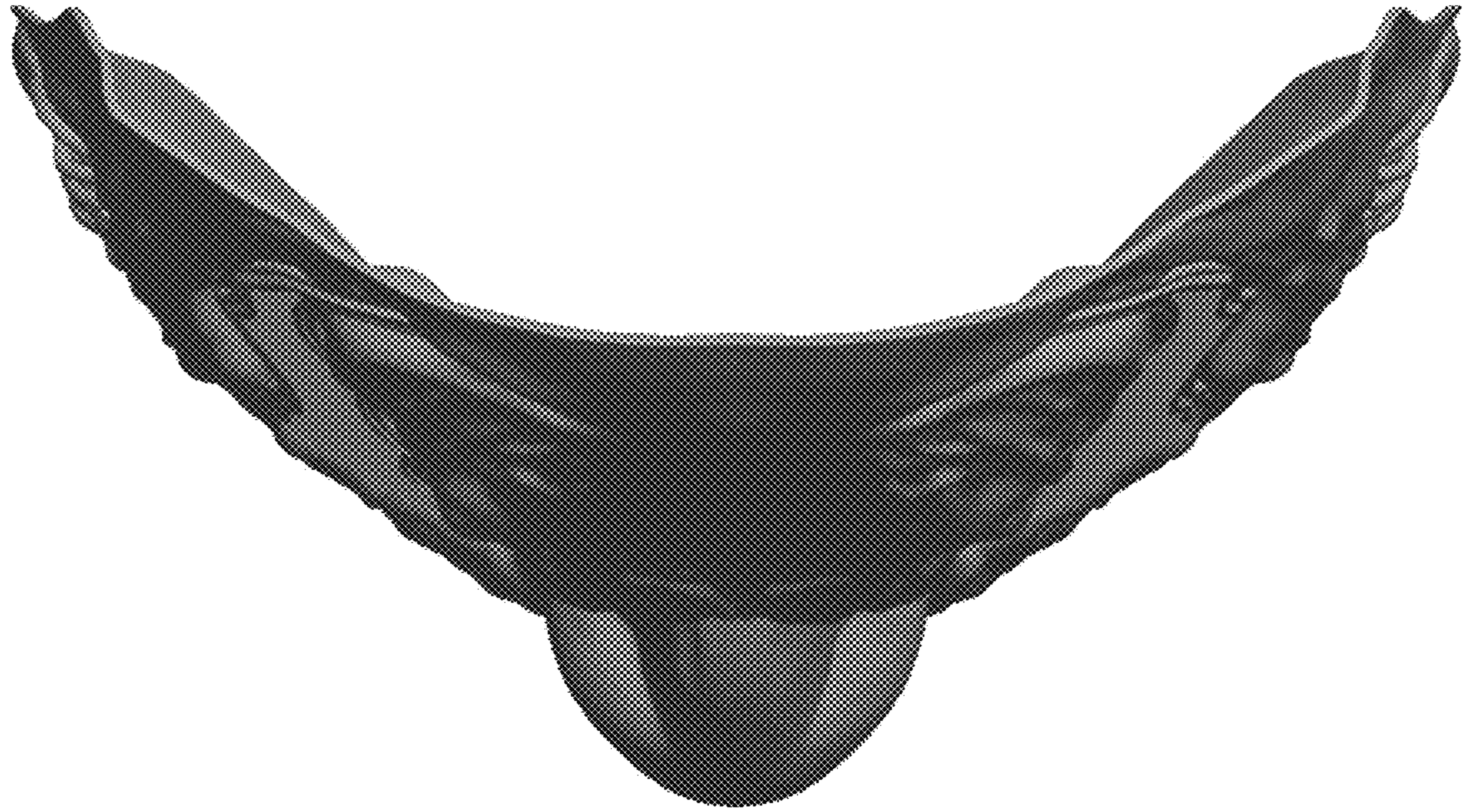


FIG. 6

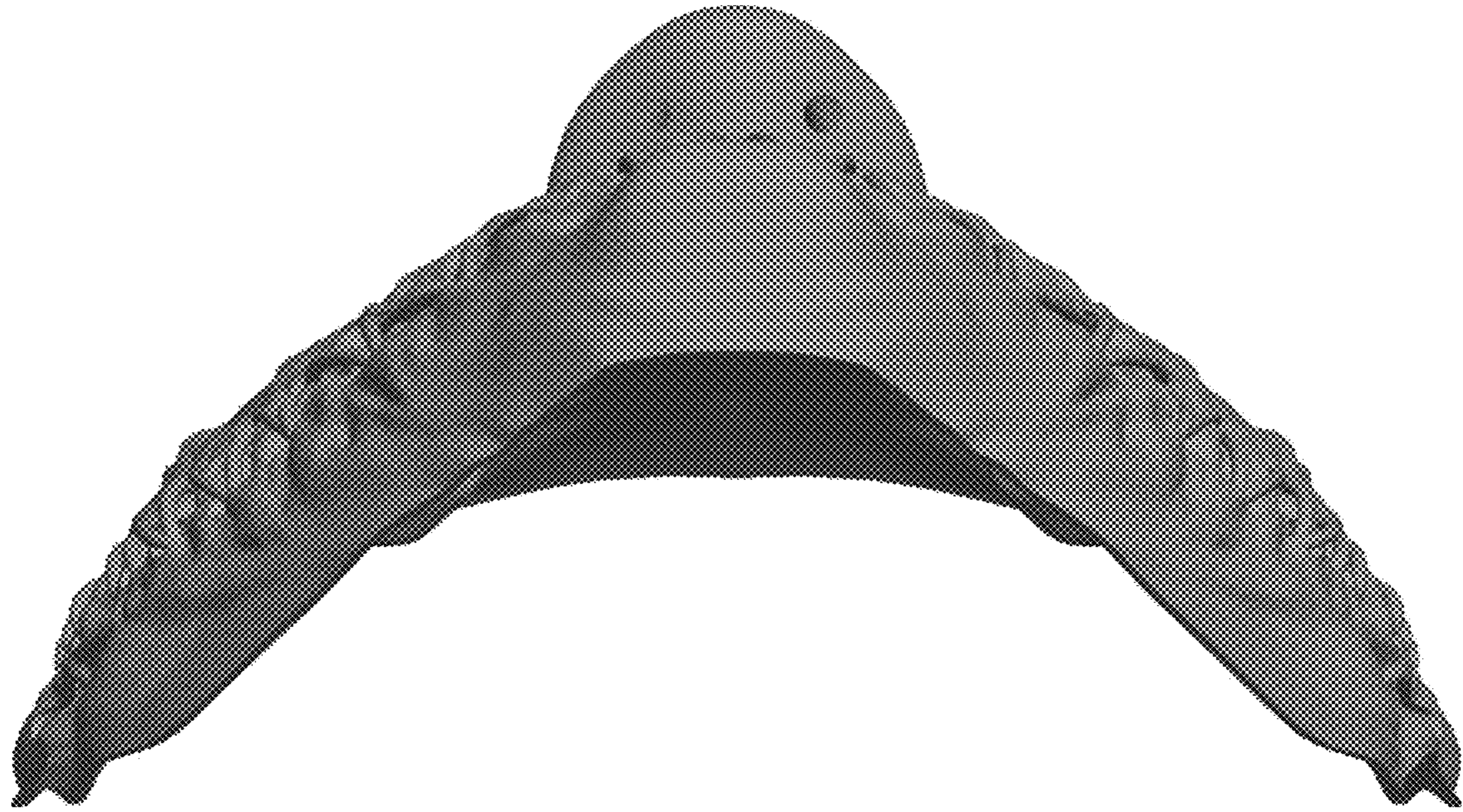


FIG. 7